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(71) Applicant (*for all designated States except US*): OTB GROUP B.V. [NL/NL]; Luchthavenweg 10, NL-5657 EB Eindhoven (NL).

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): DINGS, Franciscus, Cornelius [NL/NL]; Kapelstraat-noord 129, NL-5502 CC Veldhoven (NL). EVERSEN, Marinus, Franciscus, Johanus

[NL/NL]; Ginderover 33, NL-5591 JM Heeze (NL). HOM-PUS, Michael, Adrianus, Theodorus [NL/NL]; Dijksesstraat 33, NL-5701 AJ Helmond (NL). BLIKER, Martin, Dinant [NL/NL]; Betuwehof 64, NL-5709 KR Helmond (NL).

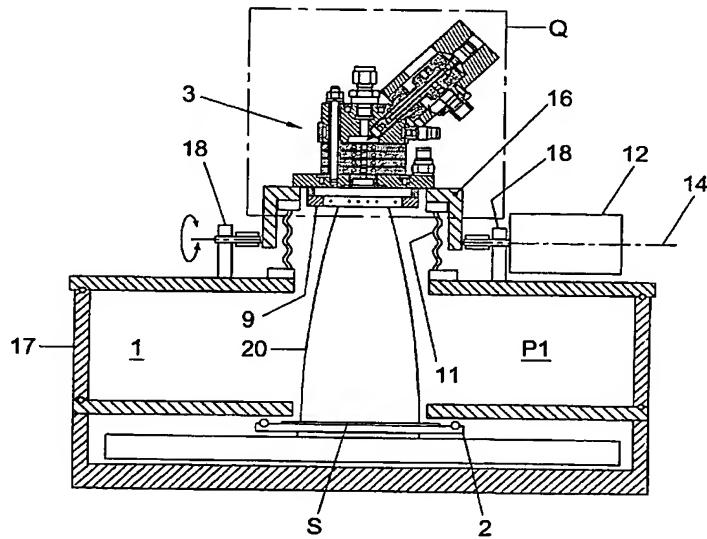
(74) Agent: PRINS, A.W.; Nieuwe Parklaan 97, NL-2587 BN Den Haag (NL).

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(54) Title: METHOD AND APPARATUS FOR TREATING A SUBSTRATE



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(57) Abstract: A method for treating a surface of at least one substrate, wherein the at least one substrate is placed in a process chamber, wherein the pressure in the process chamber is relatively low, wherein a plasma is generated by at least one plasma source, wherein, during the treatment, at least one plasma source (3) and/or at least one optionally provided treatment fluid supply source is moved relative to the substrate surface. The invention further provides an apparatus for treating a surface of at least one substrate, wherein the apparatus is provided with a process chamber and at least one plasma source, wherein the at least one plasma source (3) and/or at least one optionally provided treatment fluid supply source is movably arranged.

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